

ABSTRACT

**Lithographic apparatus with alignment subsystem, device manufacturing method
using alignment, and alignment structure**

- 5 A lithographic apparatus comprising an alignment subsystem (21) for aligning the substrate (W) on the substrate table (WT) relative to the patterning means (MA). The alignment structure (10) comprises a non-periodic feature (15) which is detectable as a capture position or a check position using a reference grating (26) in the alignment subsystem (21). The non-periodic feature (15) may cause a phase effect in the detected signal of the
- 10 alignment subsystem (21) or an amplitude effect.

[Fig. 3]